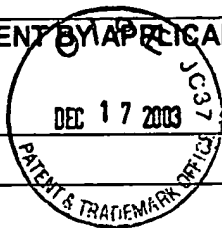


U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. 8327/ETCH/SILICON	Serial No. 10/690,318
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Mui, et al.	Confirmation No.:
(Use several sheets if necessary)		Filing Date	Group
Examiner			



U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
EC	A1	2002/0171828	11/21/2002	Cohen et al.	356	328	07/01/2002
	A2	2002/0072003	06/13/2002	Brill et al.	430	30	10/30/2001
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	A4	5,926,690	07/20/1999	Toprac et al.	438	17	
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	A7	6,245,581	06/12/2001	Bonser et al.	438	8	
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	A10	6,486,492	11/26/2002	Su	257	48	
	A11	6,501,555	12/31/2002	Ghandchari et al.	356	630	

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
EC	B1	03/003447	01/09/2003	WIPO	H01L	21/66	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
EC	C1	Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335
	C2	Raymond, "Angle-resolved scatterometry for semiconductor manufacture," Micro lithography World, Winter 2000.
	C3	Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol 3882, pg 62-65, Sept, 1999.
	C4	Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002,

Examiner

Eric Chen

Date Considered

6/20/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.